

Amendments to the Claims

This listing of claims will replace all prior versions, and listings of claims in the application:

Listing of Claims:

Claims 1-20 (Canceled)

Claim 21 (Currently Amended): A method for fabricating a semiconductor apparatus, comprising:

fabricating a semiconductor substrate having a first surface in which a semiconductor integrated circuit is formed,

the semiconductor substrate including a conductive layer formed on the first surface thereof which is connected to the semiconductor integrated circuit and including a base member of insulating material arranged between the first surface and the conductive layer,

the base member including a first surface facing the first surface of the semiconductor substrate and a second surface opposite the first surface of the base member,

the conductive layer having an extended portion extending on the second surface of the base member;

providing a connection substrate on which the semiconductor substrate is to be

mounted;

placing the semiconductor substrate so that the first surface of the semiconductor substrate faces the connection substrate;

connecting the extended portion of the conductive layer to the connection substrate; and

supplying a seal member in a space between the semiconductor substrate and the connection substrate,

wherein the base member and the seal member are made of a same material having a same thermal expansion coefficient.

Claim 22 (Previously Presented): A method according to claim 21, wherein the first surface of the semiconductor substrate is placed to face the connection substrate using a face down technique.

Claim 23 (Canceled)

Claim 24 (Previously Presented): A method according to claim 21, wherein the conductive layer and the base member constitute an electrode.

Claim 25 (Currently Amended): A method for fabricating a semiconductor apparatus comprising:

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forming a semiconductor integrated circuit on a first surface of a semiconductor substrate;

 forming a base member of insulating material on the first surface of the semiconductor substrate;

 forming a conductive layer on the first surface of the semiconductor substrate, the conductive layer being connected to the semiconductor integrated circuit and having an extended portion that extends onto a top surface of the base member;

 placing the first surface of the semiconductor substrate having the semiconductor integrated circuit, the base member and the conductive layer thereon as facing a connection substrate;

 connecting the extended portion of the conductive layer to the connection substrate; and

 supplying a sealing member in a space between the semiconductor substrate and the connection substrate, after said connecting,

wherein the base member and the sealing member are a same material.

Claim 26 (Canceled)

Claim 27 (Currently Amended): A method according to claim [[26]] 25, wherein the base member and the sealing member have a same thermal expansion coefficient.